

C¹ cont.
a passage through an outer portion of said circumferential wall.--

Amend claim 8 as follows:

C²
--8. (amended) An electrode structure comprising:
a carrier substrate having a recess disposed on a surface thereof;

a soldering land disposed in the recess, a wall of the soldering land defining an interior hollow portion and being entirely within the recess, a flange extending from an upper edge of the wall; and

at least one slit through the wall and said flange providing a passage through the wall and the flange.--

Amend claim 12 as follows:

C³
--12. (amended) An electrode structure comprising:
a carrier substrate having a recess disposed on a surface thereof;

a cup-shaped soldering land disposed in said recess, a wall of the soldering land defining an interior hollow portion, said wall being entirely within said recess; and

at least one slit through the wall extending from an upper edge of the wall and providing a passage through the wall.--
